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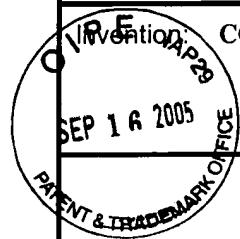
Applicant(s): Yasushi AKIYAMA et al.

Docket No.

2002JP311

Serial No.
10/519,242Filing Date
December 22, 2004Examiner
WU, Ives J.Group Art Unit
1713

COMPOSITION FOR ANTIREFLECTIVE COATING AND METHOD FOR FORMING SAME

I hereby certify that this English Language abstract of JP 60-0263141 - 1 Page
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PATENT ABSTRACTS OF JAPAN

(11)Publication number: 60-263141

(43)Date of publication of application: 26.12.1985

(51)Int.CI. G03C 1/00

G03F 7/00

(21)Application number: 59-120567 (71)Applicant: FUJI PHOTO FILM CO LTD

(22)Date of filing: 12.06.1984 (72)Inventor: KOIKE MITSURU

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TOYAMA TADAO

(54) PHOTOPOLYMERIZABLE SENSITIVE MATERIAL

(57)Abstract:

PURPOSE: To enhance storage stability under high temp. and high humidity by forming a protective layer made of a specified org. polymer and an acid.

CONSTITUTION: A photopolymerizable layer and the protective layer transmitting activated rays and substantially impermeable to oxygen and made of a polymer and an acid are laminated on a support in succession. Since PVA and a mixture of PVA and carboxymethyl cellulose are superior in impermeability to 0, they are suitable for said polymer, and as said acid, mineral acids and org. acids, preferably, such as malic acid, tartaric acid, the 2-methoxy-4-hydroxy-5-benzoylbenzenesulfonic acid, are used. Both components are dissolved in water or a solvent, such as methanol, to prepare a coating material and the protective layer is formed by coating the photopolymerizable sensitive layer.

LEGAL STATUS [Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]